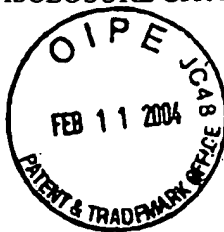


INFORMATION DISCLOSURE CITATION

Page 1 of 3 Pages



Docket: 015559-282

Appln. No.: 10/658,042

Applicant: Shuwen Guo

Filed: September 9, 2003

Group: 2878

U.S. PATENT DOCUMENTS

Examiner	Document No.	Date	Name	Class	Sub	
CH	2002/0069909	06/2002	Kubo			
CH	6,607,935	08/2003	Kwon			
CH	6,444,487	09/2002	Boggs et al.			
CH	6,305,840	10/2001	Kim et al.			
CH	6,080,987	06/2000	Belcher et al.			
CH	6,066,574	05/2000	You et al.			
CH	6,046,398	04/2000	Foote et al.			
CH	5,879,572	03/1999	Folsom et al.			
CH	5,100,479	03/1992	Wise et al.			
CH	5,056,929	10/1991	Watanabe et al.			
CH	4,959,546	09/1990	Bly			

FOREIGN PATENT DOCUMENT

						Trans	
Examiner	Document No.	Date	Country	Class	Sub	Y	N
CH	1072875	01/2001	Europe			X	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

CH	Hsieh, Ming-Chin et al., "Design and Fabrication of a Novel Crystal SiGeC Far Infrared Sensor with Wavelength 8-14 Micrometer," <u>IEEE Sensors Journal</u> , Vol. 2, No. 4, pp. 360-365 (08/2002)
CH	Taniguchi, Y. et al., "Pyroelectric Infrared Sensor Using PZT Thin Plate on Diaphragm as Sensitive Elements," <u>Electronics and Communications in Japan, Part 2</u> , Vol. 79, No. 7, pp. 86-96 (01/1996)
CH	Sánchez, S. et al., "A High T_c Superconductor Bolometer on a Silicon Nitride Membrane," <u>Journal of Microelectrochemical Systems</u> , Vol. 7, No. 1, pp. 62-67 (03/1998)

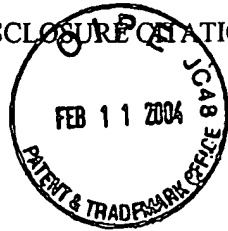
Examiner:

CONSTANTINE HANNAHER

Date Considered:

NOV 10 2005

* Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



Docket: 015559-282

Appln. No.: 10/658,042

Applicant: Shuwen Guo

Filed: September 9, 2003

Group: 2878

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

CH	Il Myun Choi et al., "A Silicon-Thermopile-Based Infrared Sensing Array for Use in Automated Manufacturing," <u>IEEE Transactions on Electron Devices</u> , Vol. ED-33, No. 1, pp. 72-79 (01/1986)
CH	Dannenberg, R. et al., "Electrical and Optical Properties of $Mn_{1.56}Co_{0.96}Ni_{0.48}O_4$," <u>SPIE</u> , Vol. 3379, pp. 158-165 (04/1998)
CH	Baliga, S. et al., "Sputtered film thermistor IR detectors," <u>SPIE</u> , Vol. 2225, pp. 72-78 (date unknown) Applicants admit the status of this publication as prior art for the limited purpose of examination of this application, but otherwise reserve the right to challenge the status of this publication as prior art. [1994]
CH	Lahiji, G.R. et al., "A Batch-Fabricated Silicon Thermopile Infrared Detector," <u>IEEE Transactions on Electron Devices</u> , Vol. ED-29, No. 1, pp. 14-22 (01/1982)
CH	Völklein, F. et al., "High-sensitivity radiation thermopiles made of Bi-Sb-Te Films," <u>Sensors and Actuators</u> , A, 29, pp. 87-91 (1991)
CH	Mirmira, S.R. et al., "Review of the Thermal Conductivity of Thin Films" <u>Journal of Thermophysics and Heat Transfer</u> , Vol. 12, No. 2, pp. 121-131 (06/1998)
CH	Shackelford, J.F. et al., "Table 77. Thermodynamic Coefficients for Oxides, page 281, <u>Materials Science and Engineering Handbook, Third Edition</u> , CRC Press (2000)
CH	Lenggenhager, R. et al., "Thermoelectric infrared sensors in CMOS technology," <u>Sensors and Actuators</u> , A, 37-38, pp. 216-220 (1993)
CH	Muller, M. et al., "A Thermoelectric Infrared Radiation Sensor with Monolithically Integrated Amplifier Stage and Temperature Sensor," <u>Transducers '95</u> , pp. 640-643
CH	Abowitz, G. et al., "The Electrical Properties of Bi:Sb:Se:Te Films," <u>Electrical Technology</u> , pp. 426-430 (07/1966)
CH	Tezcan, D.S. et al., "A Low Cost Uncooled Infrared Microbolometer Focal Plane Array Using the CMOS N-Well Layer," <u>IEEE</u> , pp. 566-569 (2001)
CH	Tezcan, D.S. et al., "An Uncooled Microbolometer Infrared Focal Plane Array in Standard CMOS," <u>SPIE</u> , Vol. 4288, pp. 112-121 (2001)
CH	Eminoglu, S. et al., "A CMOS N-Well Microbolometer FPA with Temperature Coefficient Enhancement Circuitry," <u>SPIE</u> , Vol. 4369, pp. 240-247 (2001)

Examiner:

CONSTANTINE HANNAHER

Date Considered:

NOV 10 2005

* Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITATION

Page 3 of 3 Pages



Docket: 015559-282

Appln. No.: 10/658,042

Applicant: Shuwen Guo

Filed: September 9, 2003

Group: 2878

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

CH	"CYCLOTENE – Advanced Electronics Resins, Processing Procedure, for Dry-Etch CYCLOTENE Advanced Electronics Resins (Dry-Etch BCB)," pp. 1-8, by The Dow Chemical Company (1997)
CH	Web page relating to "CYCLOTENE Dry-Etch Resins," by The Dow Chemical Company (date of first publication unknown) Applicants admit the status of this publication as prior art for the limited purpose of examination of this application, but otherwise reserve the right to challenge the status of this publication as prior art.
CH	Web page relating to "CYCLOTENE Planarization," by The Dow Chemical Company (date of first publication unknown) Applicants admit the status of this publication as prior art for the limited purpose of examination of this application, but otherwise reserve the right to challenge the status of this publication as prior art.
CH	Web page relating to "CYCLOTENE Plasma Etching," by The Dow Chemical Company (date of first publication unknown) Applicants admit the status of this publication as prior art for the limited purpose of examination of this application, but otherwise reserve the right to challenge the status of this publication as prior art.
Examiner: CONSTANTINE HANNAHER	Date Considered: NOV 10 2005

* Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609.

Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.